



AC microLine[®] 2000-P³

PRIME WAFER DOUBLE-SIDE POLISHING SYSTEM



THE MOST COMPREHENSIVE SOLUTION



)Unique and patented UPAC (Upper Platen Adaptive Control) System



2 Gap Sensors



Benchmark in precision, quality, efficiency, and cost of ownership



The most flexible machine for supporting all future wafer requirements

BENCHMARK IN PRECISION AND FLEXIBILITY

enhancing surface quality





HIGHLIGHTS AC microLine[®] 2000-P³

- Unique and patented UPAC (Upper Platen Adaptive Control) System
- Monitoring of the cooling lubricant flow rate
- Loop control

- First-Class customer support for the highest machine availability and productivity
- Integrated high precision interferometric device for in-situ measurement of the wafer thickness
- High-Pressure Conditioner
- Slurry Recycling Station
- Slurry Pressure Distribution
- Integrated Process Data Recording (DataCare[®])
- Industry 4.0
- Touch Screen



The importance of the gap – Perfect wafer flatness requires gap adjustment



UPAC System – Global Measurement



SFQR Map – 300 mm Si-Wafer SFQR Values: Max: 11.59 nm, Average: 5.98 nm

TECHNICAL DATA	AC microLine® 2000-P ³
Wheel diameter [mm]	1935
Ring width [mm]	686
Max. load pressure [daN]	4000
Upper/lower drive power [kW]	46
Upper/lower drive speed [rpm]	0-40
Center drive power [kW]	7.5
Center drive speed [rpm]	0–50
Outer drive power [kW]	9.5
Outer drive speed [rpm]	0-7.5
Working wheel cooling	Labyrinth
Dimensions [H×W×D] [mm]	3000×4200×3900
Weight [kg]	21000
Load capacity 300 mm [12"] Wafer 200 mm [8"] Wafer	15 pieces 30 pieces

GET IN TOUCH WITH US TODAY TOGETHER WE WILL FIND A SOLUTION FOR YOUR REQUIREMENTS

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